New ALD processes for Y_2O_3 using molecularly engineered yttrium formamidinates

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Associated Publication:

A study on the influence of ligand variation on formamidinate complexes of yttrium: new precursors for atomic layer deposition of yttrium oxide
Beer *et al.*, *Dalton Trans.*, **2021**, 50, 12944-12956, DOI: 10.1039/d1dt01634b

Atomic layer deposition of dielectric Y_2O_3 thin films from a homoleptic yttrium formamidinate precursor and water
Boysen *et al.*, *RSC Adv.*, **2021**, 11, 2565-2574, DOI: 10.1039/d0ra09876k.